

## Supplementary Information

# Nanoridge patterns on polymeric film by photodegradation copying method for metallic nanowire networks

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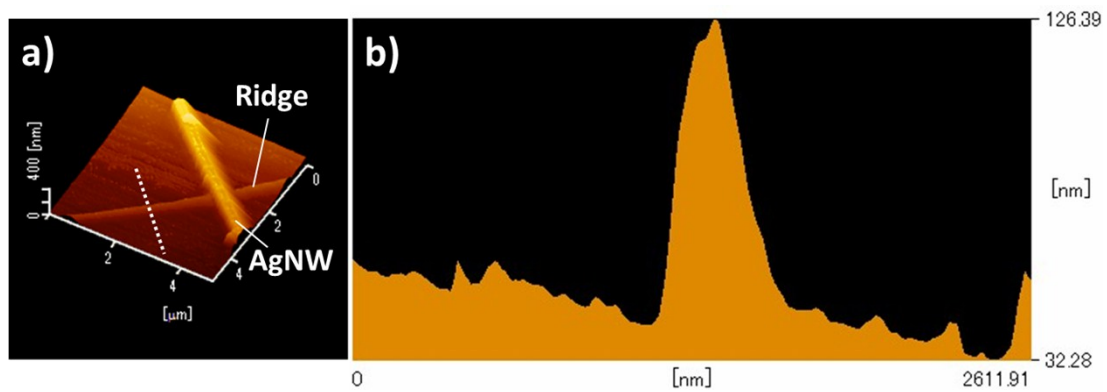
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**Figure S1.** The AFM image of the AgNW and ridge on PET film. (a) the bare PET area, the AgNW and the ridge once shielded by AgNW; (b) the roughness along the dash line in (a).